

Page 8, line 5 to page 8, line 10, delete current paragraph and insert therefor:

A2
In this case, the first gas pressure is, for example, 900 hPa to 1100 hPa, i.e., approximately 1 atm. (atmospheric pressure). The second gas pressure is, for example, within a range of 50 Pa to 10 kPa, i.e., approximately 0.1 to 0.01 atm. It is unnecessary that the second gas pressure is extremely in the high vacuum.

Page 8, line 11 to page 8, line 24, delete current paragraph and insert therefor:

A3
In another aspect, a second exposure method according to the present invention resides in an exposure method for illuminating a first object with an exposure light beam and exposing a second object with the exposure light beam having passed through a pattern on the first object; the exposure method comprising tightly enclosing a space which includes at least a part of an optical path for the exposure light beam; the exposure method further comprising a first step of substituting the tightly enclosed space with a first gas through which the exposure light beam is transmitted; and a subsequent second step of substituting the tightly enclosed space with a second gas through which the exposure light beam is transmitted, the second gas being different from the first gas.

Page 9, line 7 to page 9, line 21, delete current paragraph and insert therefor:

A4
In still another aspect, a first exposure apparatus according to the present invention resides in an exposure apparatus for illuminating a first object with an exposure light beam and exposing a second object with the exposure light beam having passed through a pattern on the first object; the exposure apparatus comprising a gas-tight chamber which tightly encloses a space including at least a part of an optical path for the exposure light beam; and a gas supply unit which supplies a predetermined gas through which the exposure light beam is transmitted, to interior of the gas-tight chamber; wherein the gas supply unit has an impurity-removing filter including a light-absorbing gas-removing filter which removes at least one of oxygen and steam contained in the predetermined gas.

Page 10, line 1 to page 10, line 17, delete current paragraph and insert therefor:

A5
In still another aspect, a second exposure apparatus according to the present invention resides in an exposure apparatus for illuminating a first object with an exposure light beam and exposing a second object with the exposure light beam having passed through a pattern on the first object; the exposure apparatus comprising a gas-tight chamber which tightly encloses a space including at least a part of an optical path for the exposure light beam; a gas supply unit which supplies a predetermined gas through which the exposure light beam is transmitted, to interior of the gas-tight chamber; a gas concentration-measuring unit which measures a concentration of a predetermined residual gas remaining in the space in the gas-tight chamber; and an opening/closing mechanism which opens/closes a passage for the gas between the space in the gas-tight chamber and the gas concentration-measuring unit.

Page 11, line 1 to page 11, line 26, delete current paragraph and insert therefor:

A6
In still another aspect, a third exposure apparatus according to the present invention resides in an exposure apparatus for illuminating a first object with an exposure light beam and exposing a second object with the exposure light beam having passed through a pattern on the first object; the exposure apparatus comprising a gas-tight chamber which tightly encloses a space including at least a part of an optical path for the exposure light beam; a gas supply unit which supplies a predetermined gas through which the exposure light beam is transmitted, to interior of the gas-tight chamber; an openable/closable cutoff valve which is provided in a supply passage for the predetermined gas to be supplied by the gas supply unit; and a control unit which closes the cutoff valve in case of emergency and in case of maintenance for the exposure apparatus to stop the supply of the predetermined gas to the gas-tight chamber. According to the exposure apparatus as defined above, the interior of the gas-tight chamber can be filled with the gas through which the exposure light beam is transmitted, in a short period of time by closing the cutoff valve in case of emergency and in case of maintenance, introducing the external air into the gas-tight chamber to perform predetermined operation, and then opening the cutoff valve again. Therefore, it is possible to